

NMLS

Nano-Micro-Lithography Symposium

Preliminary Agenda

Date: Wednesday, October 19th 14:00 - 17:05 CEST
Thursday, October 20th 9:00 - 13:00 CEST
Place: Online on gather.town

October 19 th , 2022		
Nezih Ünal & Helge Mischke GenISys / micro resist	Welcome & Introduction	14:00
Keynote Speaker Dr. Robert Kirchner TU Dresden	Multi-material 3D printing using 2-photon laser direct writing	14:10
Dr. Maria Russew micro resist technology	Micro- and nanostructuring of hybridpolymers for various applications	14:45
	Coffee Break & Online Job fair	15:10
Dr. Christian Helke Fraunhofer ENAS	Challenges for integration of optical elements	15:50
Dr. Muhammad Refatul Haq Paul Scherrer Institut	Vertical sidewalls in thick epoxy resists – a challenge for laser-based direct write lithography	16:15
Dr. Kahraman Keskinbora Raith GmbH, MIT, USA	Randomized Fresnel Zone Plates for EUV Free-electron lasers fabricated with ion beam lithography	16:40
	End of Day 1	17:05
October 20 th , 2022		
Nezih Ünal & Helge Mischke GenISys / micro resist	Welcome & Introduction	09:00
Keynote Speaker Prof. Angelo Accardo Delft University of Technology	The era of two-photon polymerized engineered microenvironments, a promising tool for cell mechanobiology and in-vitro disease/treatment modelling	09:10
Dr. Sven Bauerdick GenISys	ProSEM Metrology Software: New Automation Features and Improvements	09:45
Dr. Jochen Zimmer Nanoscribe	2.5D and 3D microfabrication with nanoprecision alignment and tilt compensation	10:10
	Coffee Break & Online Job fair	10:35
Prof. Wolfram Pernice University of Münster, University of Heidelberg	3D-coupling interfaces for photonic quantum technologies	11:15
Viacheslav Vlasenko Raith GmbH	PICOMASTER laser lithography systems: sub 300nm exposure capabilities	11:40
	Discussion and Networking	12:05
	End of Day 2	13:00